



Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (currently amended) A vacuum processing apparatus comprising:
 - two processing chambers disposed adjacent one another, each processing chamber being configured with a top, bottom and side wall portions which are separate from said adjacent processing chamber and having a processing table for supporting an object to be processed and carrying out processing using a gas;
 - a transfer unit coupled to said two adjacent processing chambers which transfers the object to be processed at least one of to and from at least one of said two adjacent processing chambers, each of said two adjacent processing chambers being detachably coupled on one respective side wall portion thereof to said transfer unit; and
 - a mass flow controlling unit disposed between the side wall portions of said two adjacent processing chambers for directly supplying gas to each of said two adjacent processing chambers for enabling processing of the object to be processed when supported on the processing table thereof.

Claims 2 - 6 (canceled)

7. (previously presented) A vacuum processing apparatus according to claim 1, wherein the mass flow controlling unit is disposed between said two adjacent processing chambers without being fluidly connected to the transfer unit.

8. (previously presented) A vacuum processing apparatus according to claim 7, wherein the mass flow controlling unit includes a first mass flow controlling device for supplying gas to one of said two adjacent processing chambers and a second mass flow controlling device for supplying gas to another of said two adjacent processing chambers, said first mass flow controlling device and said second mass flow controlling device being disposed with respect to one another in a vertical direction.

Claim 9 (canceled)

10. (currently amended) A vacuum processing apparatus comprising:

two vacuum processing chambers disposed adjacent one another and, each of the two vacuum processing chambers being configured with a top, bottom and side wall portions which are separate from the adjacent vacuum processing chamber and being respectively detachably connected to the vacuum processing apparatus, the two adjacent vacuum processing chambers being supplied with a processing gas to generate plasma utilized for processing a wafer disposed therein; and

plural controllers which control the supply of the processing gas directly into each of the two adjacent vacuum processing chambers so as to enable processing of the wafer disposed therein, the plural controllers being disposed between the side wall portions of the two adjacent vacuum processing chambers.

11. (currently amended) A vacuum processing apparatus according to claim 10, further comprising a transfer unit enabling transfer of the wafer, wherein each of the two adjacent vacuum processing chambers are-is detachably connected on one

respective side wall portion thereof to the transfer unit so as to enable transfer of the wafer between a respective vacuum processing chamber and the transfer unit.

12. (previously presented) A vacuum processing chamber according to claim 11, wherein the transfer unit has a polygonal shape in plan view, and each of the two adjacent vacuum processing chambers are disposed on respective side walls forming two adjacent sides of the polygonal shape of the transfer unit.

13. (previously presented) A vacuum processing apparatus according to claim 10, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers directly supplying gas to one of the two adjacent vacuum processing chambers and the other of the plural controllers directly supplying gas to the other of the two adjacent vacuum processing chambers.

14. (previously presented) A vacuum processing apparatus according to claim 10, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

15. (previously presented) A vacuum processing apparatus according to claim 13, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.

16. (previously presented) A vacuum processing apparatus according to claim 11, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers directly supplying gas to one of the two

adjacent vacuum processing chambers and the other of the plural controllers directly supplying gas to the other of the two adjacent vacuum processing chambers.

17. (previously presented) A vacuum processing apparatus according to claim 11, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

18. (previously presented) A vacuum processing apparatus according to claim 17, wherein the plural controllers are detachable from the vacuum processing apparatus as one unit.

19. (previously presented) A vacuum processing apparatus according to claim 12, wherein the plural controllers are disposed adjacent one another in a vertical direction, one of the plural controllers directly supplying gas to one of the two adjacent vacuum processing chambers and the other of the plural controllers directly supplying gas to the other of the two adjacent vacuum processing chambers.

20. (previously presented) A vacuum processing apparatus according to claim 12, wherein the plural controllers are disposed in a space between the two adjacent vacuum processing chambers.

Claims 21 and 22 (canceled)

Claims 23 and 24 (canceled)

25. (new) A vacuum processing apparatus according to claim 1, wherein each of the two adjacent vacuum processing chamber is detachably connected on another side wall portion thereof to the mass flow controlling unit.

26. (new) A vacuum processing apparatus according to claim 10, wherein each of the two adjacent vacuum processing chambers is detachably connected on another side wall portion thereof to the one of the plural controllers.

27. (new) A vacuum processing apparatus according to claim 1, wherein said transfer unit further enables transfer of the object to be processed between an atmospheric unit which holds the object to be processed outside of said transfer unit and at least one of to and from at least one of said two adjacent processing chambers through said transfer unit.

28. (new) A vacuum processing apparatus according to claim 11, wherein the transfer unit further enables transfer of the object to be processed between an atmospheric unit which holds the object to be processed outside of the transfer unit and at least one of to and from at least one of the two adjacent vacuum processing chambers through the transfer unit.